

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re U.S. Patent Application of)
KIKAWA et al.)
Application Number: To be Assigned)
Filed: Concurrently Herewith)
For: LASER DIODE AND MANUFACTURING METHOD)
THEREOF)
ATTORNEY DOCKET NO. NITT.0186)

**Honorable Assistant Commissioner
for Patents
Washington, D.C. 20231**

INFORMATION DISCLOSURE STATEMENT

Sir:

Pursuant to 37 C.F.R. §§ 1.56 and 1.97, this Information Disclosure Statement is submitted in the above-identified patent application. A listing of documents to be published on the face of any patent granted from this application is submitted herewith on Form PTO-1449. Any other documents or information submitted for consideration by the Examiner are listed in this paper. A copy of each U.S. and foreign patent, or each publication or portion thereof listed or herein identified, submitted herewith.

This Information Disclosure Statement is submitted with the initial filing of the application. Accordingly, no fee is due or payable at this time.

The Examiner is requested to acknowledge consideration of the information provided in this paper in accordance with prescribed procedures.

Please charge any additional fees or credit any overpayments in connection
with this paper to Deposit Account No. 08-1480.

Respectfully submitted,

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Form PTO 1449 U.S. Department of Commerce Patent and Trademark Office Information Disclosure Statement by Applicant	ATTY. DOCKET NUMBER NITT.0186	SERIAL NUMBER To be Assigned
	APPLICANT KIKAWA et al.	
	FILING DATE Concurrently Herewith	GROUP

U.S. Patent Documents

Examiner Initial	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	5,063,173	11/5/91	Gasser et al.			6/15/90

Foreign Patent Documents

Other Documents (Including Author, Title, Date Pertinent Pages, Etc.)

		Tonao Yuasa et al., "Facet Protection of (AlGa)As Lasers Using SiO ₂ Sputter Deposition", Appl. Phys. Lett, Vol. 34, No. 10, (May 15, 1979), pp. 685-687
EXAMINER		DATE CONSIDERED

EXAMINER: Initial if citation is considered, whether or not citation is in conformance with MPEP 609; draw a line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant